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Construction of thickness-controllable bimetallic sulfides/reduced graphene oxide as a binder-free positive electrode for hybride supercapacitors

Ramage M. Ghanem^a, Doaa A. Kospa^a, Awad I. Ahmed^a, Amr Awad Ibrahim^{a*},
Ahmed Gebreil^b

^a*Department of Chemistry, Faculty of Science, Mansoura University, Al-Mansoura 35516, Egypt.*

^b*Nile Higher Institutes of Engineering and Technology, El-Mansoura, Egypt.*

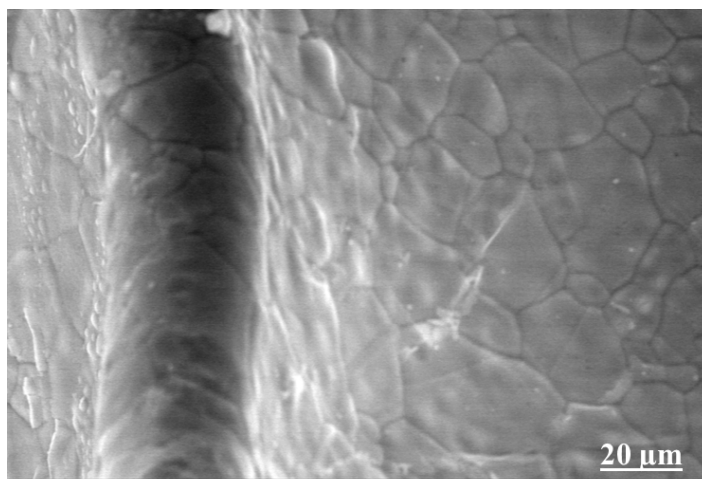


Fig. S1: SEM images of NiCuS/5rGO/NF deposited at controllable CV cycles.

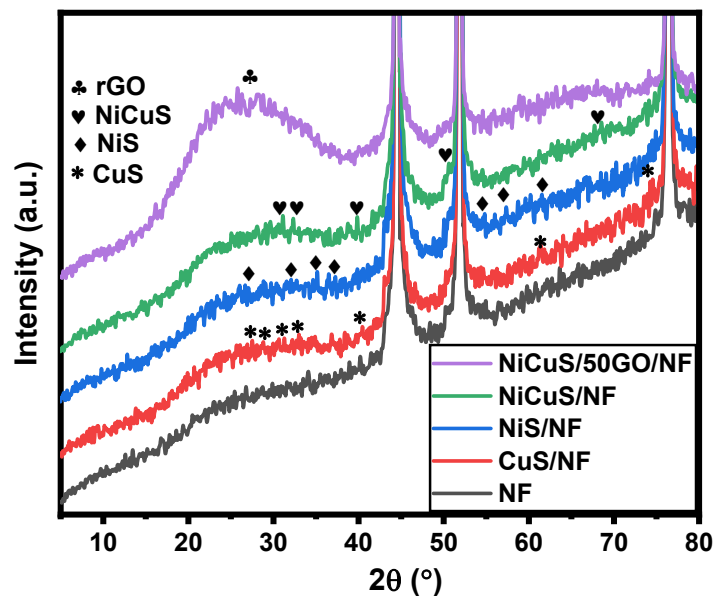


Fig. S2: FT-IR spectra of the as-synthesized materials.

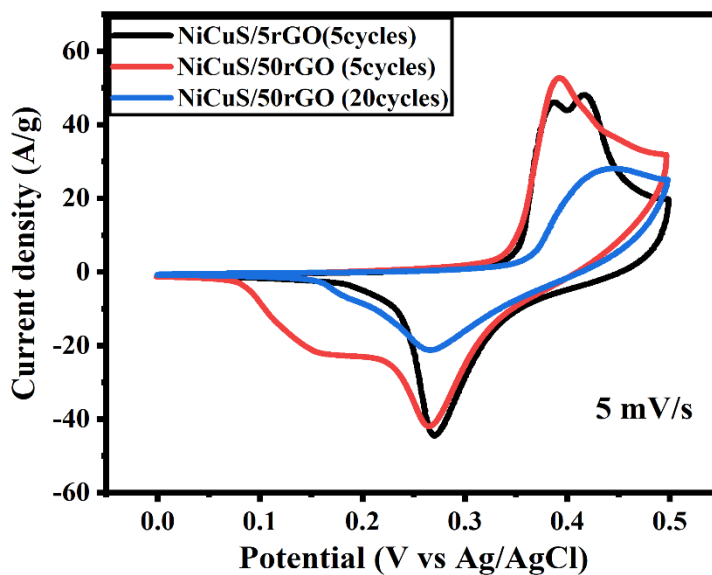


Fig. S3: CV of NiCuS/5rGO and NiCuS/50rGO (5 cycles) and NiCuS/50rGO (20 cycles) at scan rate 5mV/s.

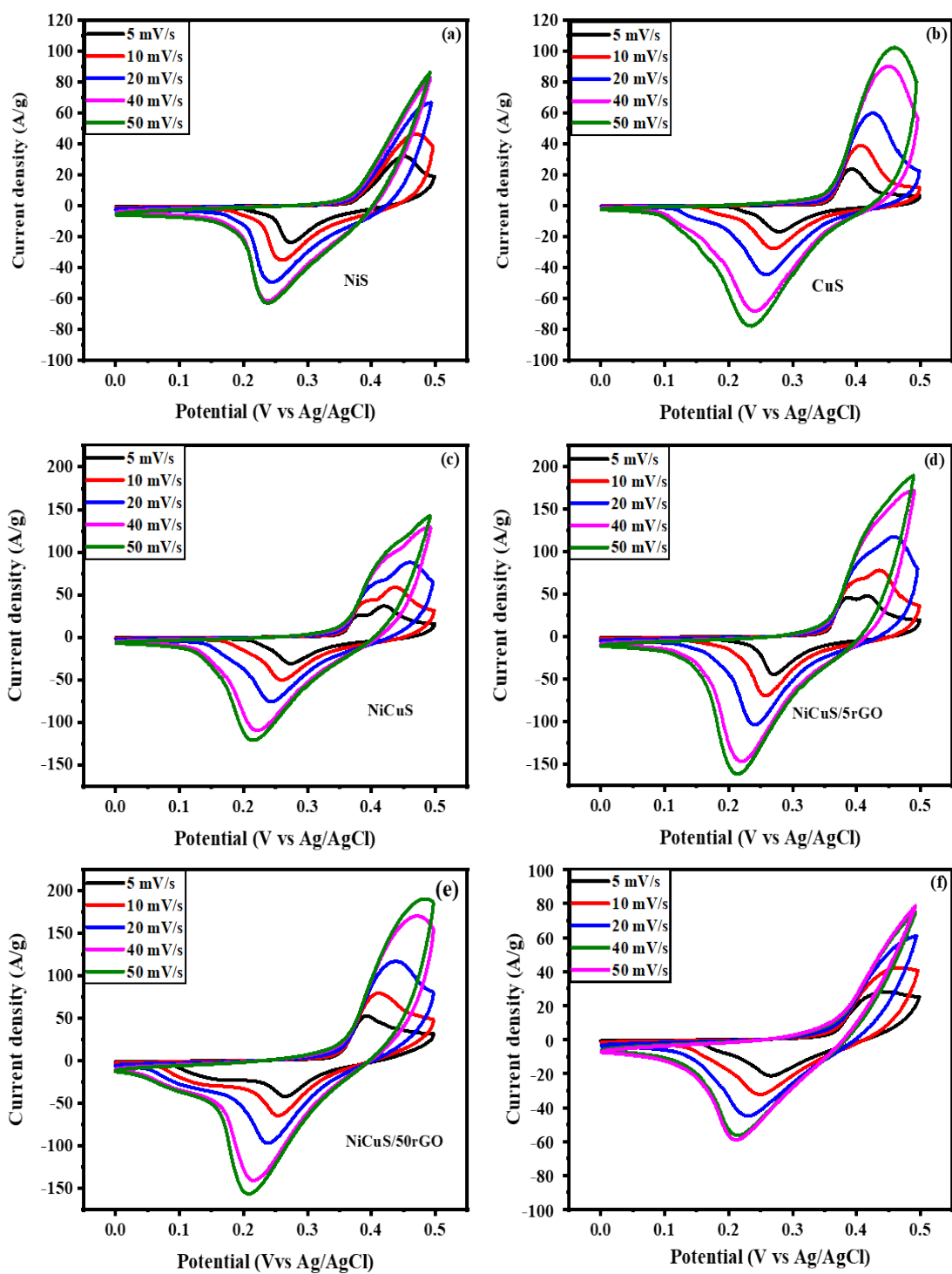


Fig. S4: The CV curves of (a) NiS, (b) CuS, (c) NiCuS, (d) NiCuS/5rGO, (e) NiCuS/50rGO (5 cycles), and (f) NiCuS/50rGO (20 cycles) electrodes in the range of 0.0V-0.5V at different scan rates.

Determination of Electrochemically Active Surface Area (ECSA) of electrocatalysts

The electrical double layer (EDL) capacitance was used to assess the ECSA of the deposition electrodes. In a limited potential window, all electrode CV curves at various scan rates were recorded, as illustrated in S4. The capacitive current (i_c) should be in direct proportion to the scan rate (v):¹

$$i_c = vC_{EDL} \quad (1)$$

where C_{EDL} represents EDL capacitance. Assuming the areal EDL capacitance of carbon (C^*) is $13 \mu\text{F}/\text{cm}^2$ as reported by Ji et al.

To calculate the ECSA, the following equation was applied:

$$ECSA = C_{EDL}/C^* \quad (2)$$

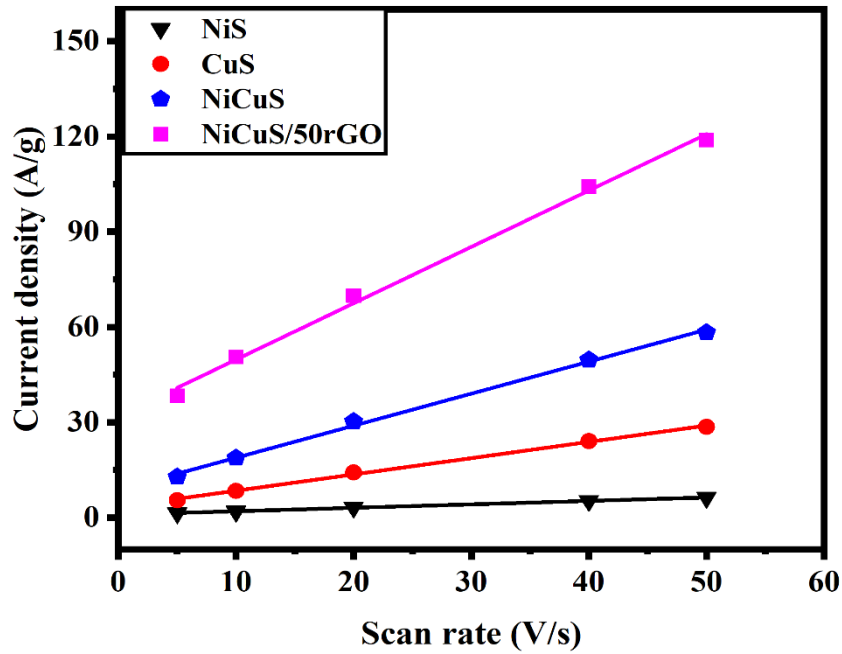


Fig. S5: Capacitive current- scan rate plot of all catalysts.

Table. S1: Comparison of previous reports on metal sulfides for supercapacitors with the

Material	Synthesis	Electrolyte	Capacitance	Condition	Retention	No. of Cycle	Ref.
NiCu ₂ S ₂ /NF	Cathodic vacuum arc technique	2 M KOH	1975.2 C/g	0.5 mA/cm ²	76.8% at 10 mA/cm ²	3000	²
NiCu/NF	Cathodic vacuum arc technique	2 M KOH	739.6 C/g	0.5 mA/cm ²	48.3% at 10 mA/cm ²	3000	²
Ni _{0.8} Cu _{0.2} S/CC	Hydrothermal	2 M KOH	938.6 F/g	1 A/g	69 % at 2 A/g	10000	³
NiCuS/NF	Hydrothermal	3 M KOH	2.14 F/cm ²	1mA/cm ²	72.2% at 50 mA/cm ²	10000	⁴
NiCoS/GO/NF	situ chemical transformation	6 M KOH	1492 F/g	1 A/g	96% at 6 A/g	8000	⁵
CuMnS//AC	electrodeposition	1 M KOH	1691 F/g	10 A/g	94% at 20 A/g	2500	⁶
Annealed-Co ₃ O ₄	Electrodeposition	1 M KOH	621F/g	5 mA/cm ²	91.4% at 5 mA/g	4000	⁷
2D- ZnS/FeS @carbon cloth (CC)	Hydrothermal	6 M KOH	1367.5 F/g	3 A/g	87% at 15 A/g	5000	⁸
CoS ₂ -rGO//N-CNT	Hydrothermal	1 M KOH	1417 F/g	2 A/g	92% at 10 A/g	5000	⁹
NiMn ₂ O ₄ @CoS//SCG	electrodeposition	1 M KOH	1727 F/g	1 A/g	94 % at 10 A/g	5000	¹⁰
CuS-NHS (nano hollow sphere)	hydrothermal method	6 M KOH	948 F/g	1 A/g	90.9% at 2 A/g	1000	¹¹
NiS/GO	hydrothermal method	2 M KOH	905.3 F/g	0.5 A/g	90.9% at 4 A/g	2000	¹²
CuS Nanorods	hydrothermal method	6 M KOH	179 F/g	1 A/g	41% at 2 A/g	1000	¹¹
NiCuS/50rGO//AC	Electrodeposition	1 M KOH	920.1 C/g	1 A/g	96.2% at 10 A/g	10000	This work

fabricated NiCuS/rGO.

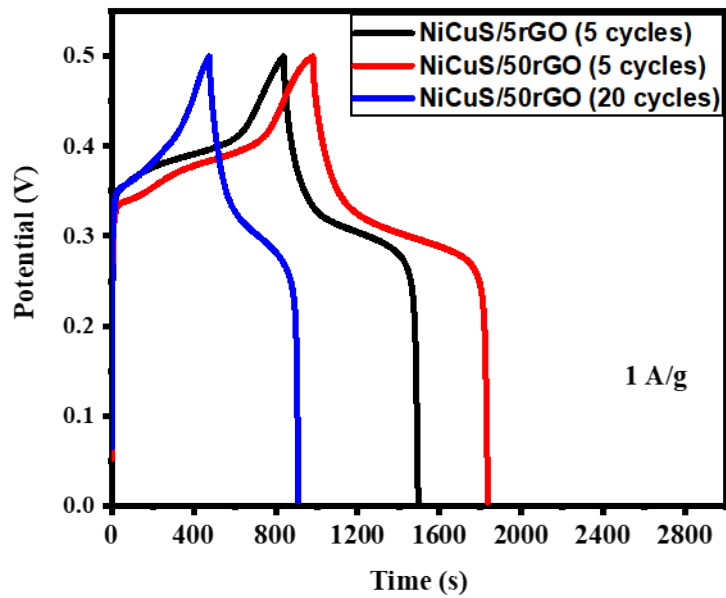


Figure S6: Comparison of the GCD curves of NiCuS/5rGO (5 cycles), and NiCuS/50rGO (5 and 20cycles).

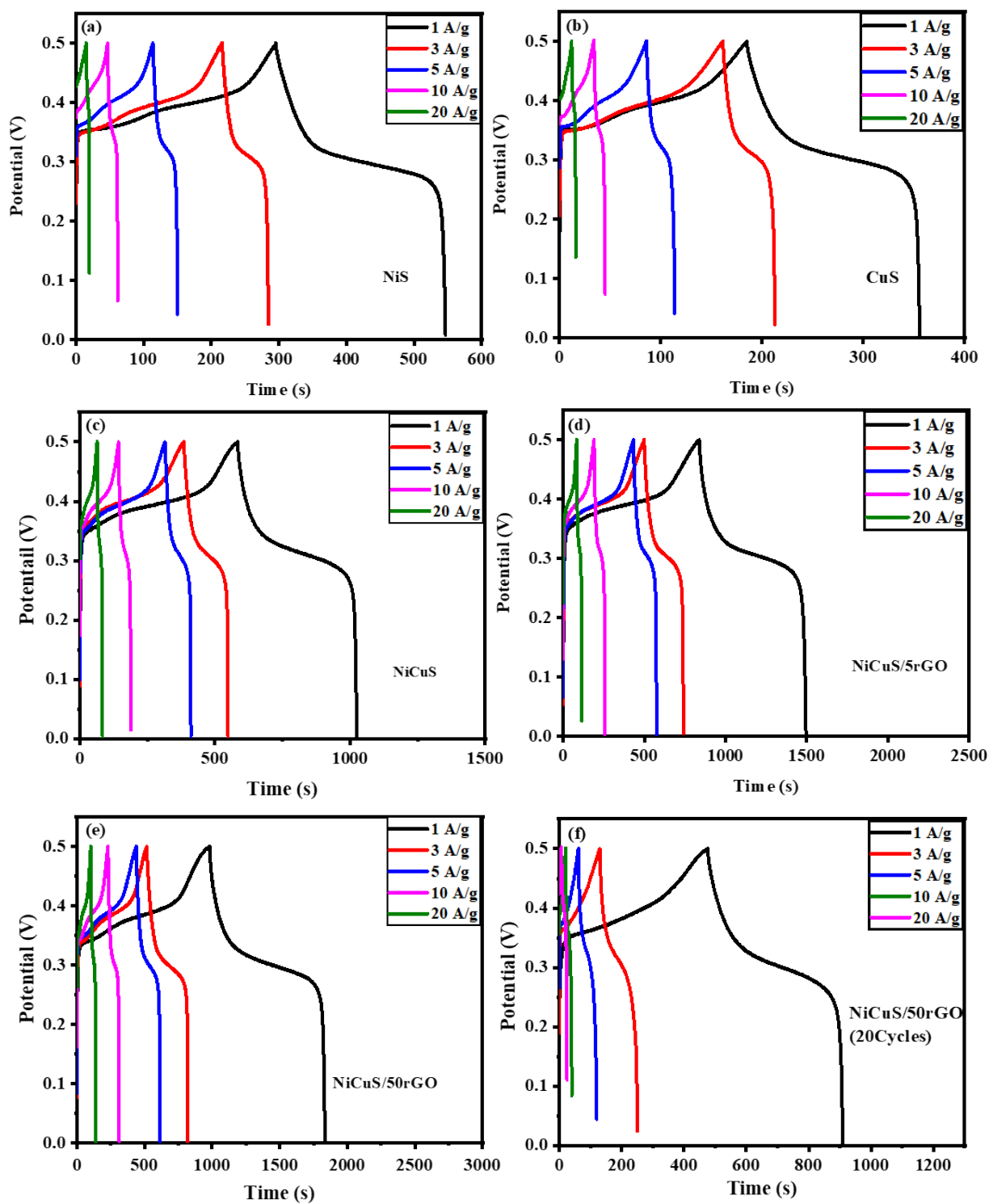


Figure S7: GCD curves of (a) NiS, (b) CuS, (c) NiCuS, (d) NiCuS/5rGO, (e) NiCuS/50rGO (5 cycles), and (f) NiCuS/50rGO (20 cycles) at different current densities.

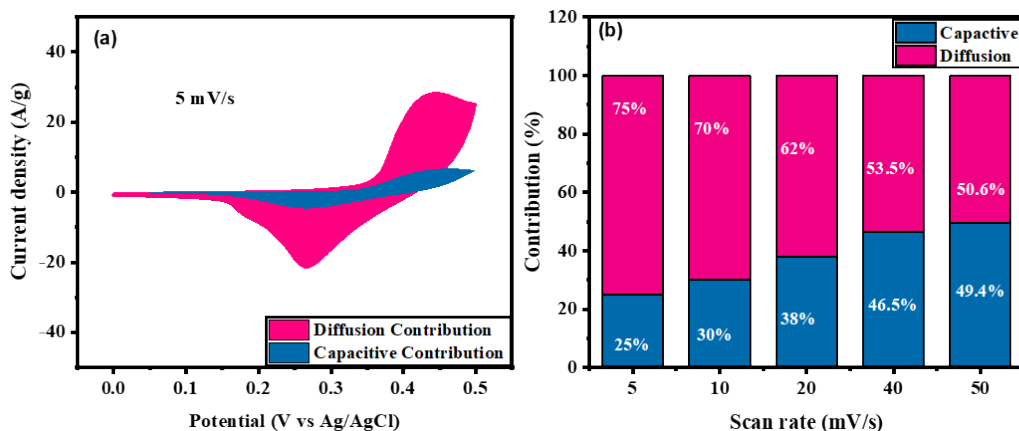


Fig. S8: (a) CV plots of diffusion/ capacitive-controlled contributions at 5mV/s and (b) the ratio of diffusion/ capacitive-controlled contributions as a function of scan rate for NiCuS/50rGO (20 cycles).

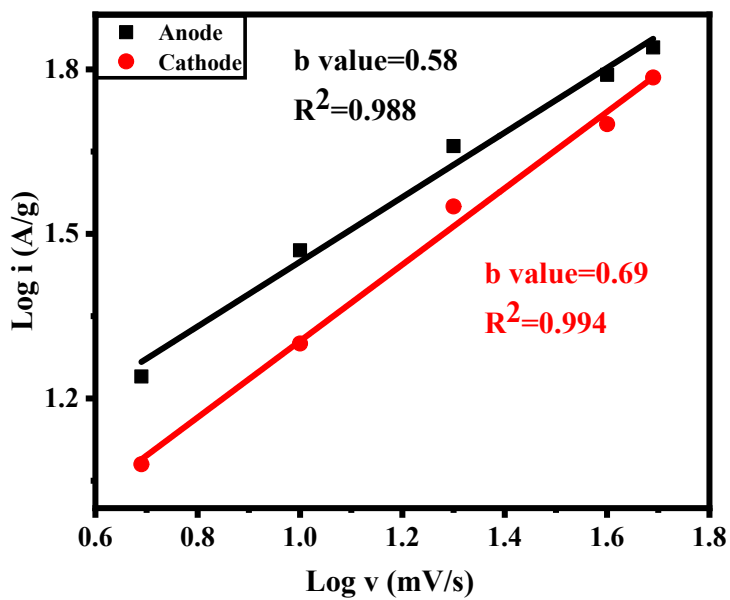


Fig. S9: The relationship between the log (i) and the log(v) of NiCuS/50rGO (50 cycles).

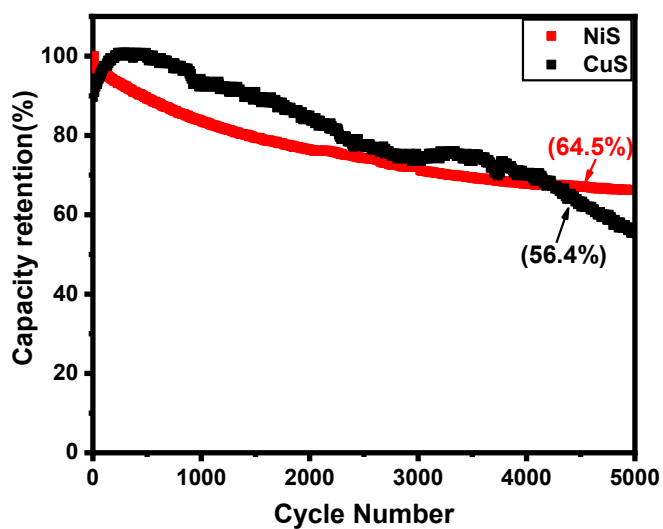


Fig. S10: Cycling stability comparison of NiS and CuS electrodes at 20 A/g.

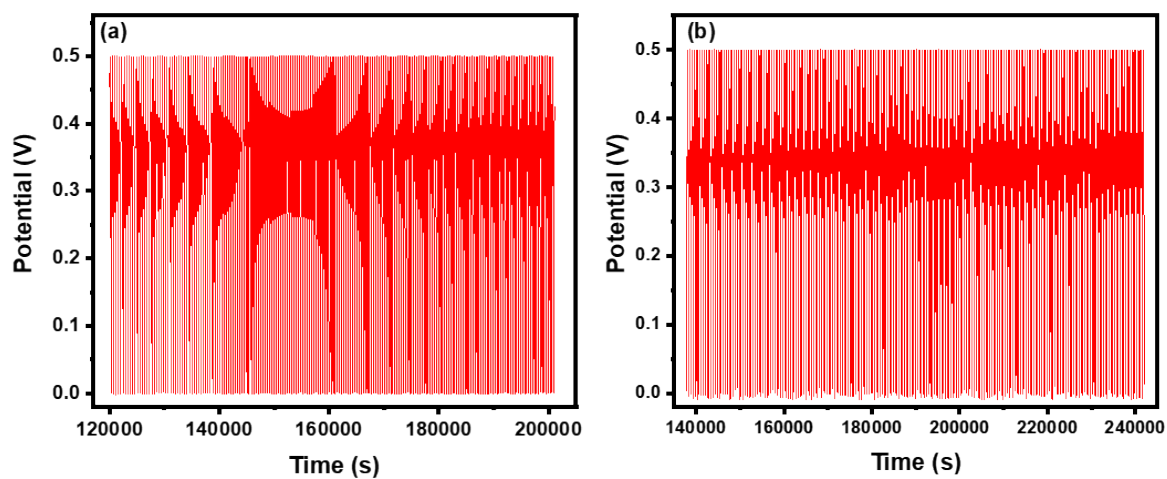


Fig. S11: GCD stability test for (a) NiCuS and (b) NiCuS/50 rGO (5 cycles) for 5000 cycles at 20 A/g current density.

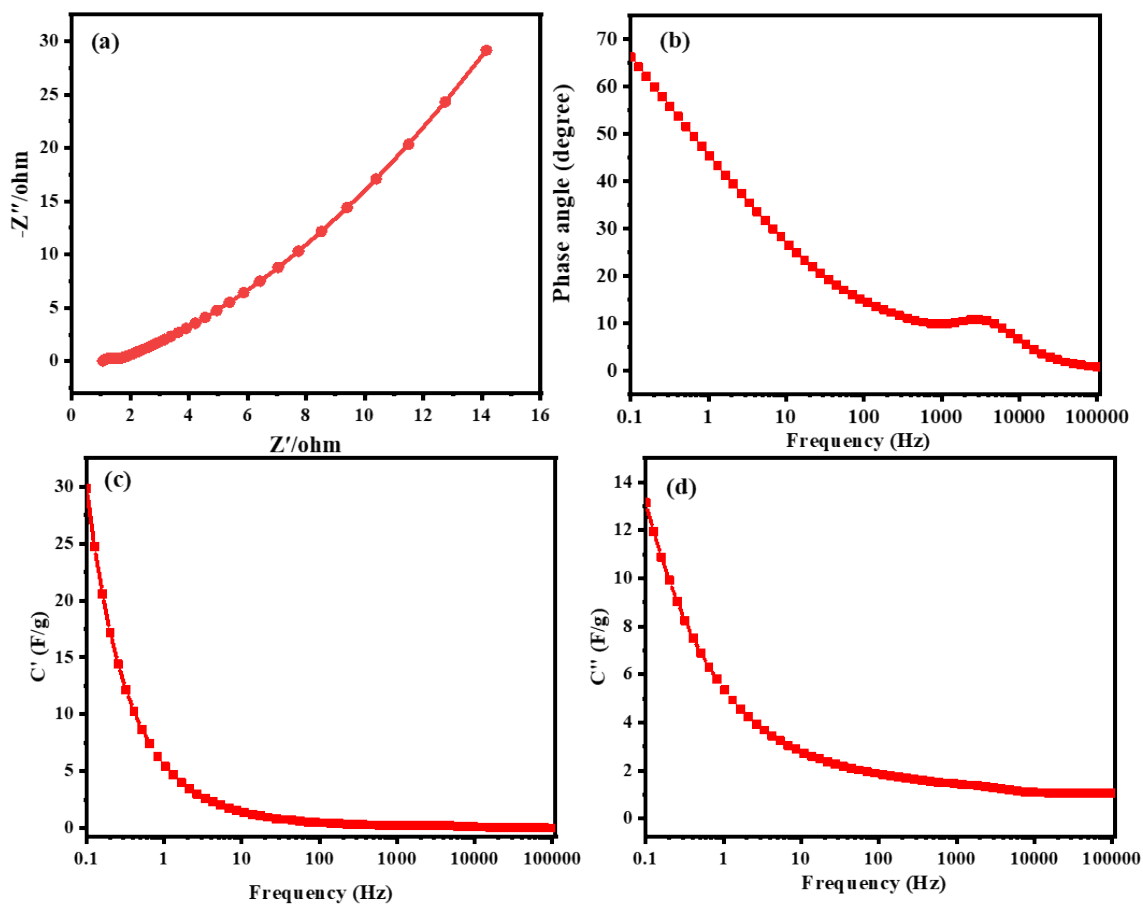


Fig. S12: Nyquist plots of NiCuS/50rGO/NF//AC device from 0.1 Hz to 100 kHz in 0.1 KOH. (a), Bode plots (b), and the real (c) and imaginary (d) capacitances of device versus frequency.

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